

16W 2818

[10191/4116]

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s) : LAERMER et al.  
Serial No. : 10/524,610  
Filed : August 11, 2005  
For : LAYER SYSTEM HAVING A SILICON LAYER AND A  
PASSIVATION LAYER, METHOD FOR CREATING A  
PASSIVATION LAYER ON A SILICON LAYER AND ITS USE  
Art Unit : 2818  
Examiner : HO, Hoang Quan Tran  
Confirmation No. : 9981  
Customer No. : 26646

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

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Date: October 11, 2006

Signature:

Jong H. Lee (R. No. 36,197)

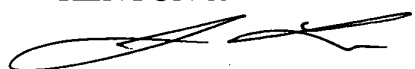
**RESPONSE TO RESTRICTION REQUIREMENT**

SIR:

In response to the requirement for restriction contained in the Office Action dated September 15, 2006, Applicants elect Invention I (claims 16-28) directed to a layer system, for further prosecution on the merits.

Respectfully submitted,

KENYON & KENYON LLP

 (R. No. 36,197)

Dated: October 11, 2006

By: JONG LEE & Gerard Messina  
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